

IN THE ABSTRACT

Please replace the Abstract, as filed, with the revised Abstract, submitted concurrently herewith.

ABSTRACT

A lithographic projection apparatus is presented, which includes a housing, which comprises therein a first exposure system that has at least one movable part (*e.g.* a movable first substrate holder or a movable second substrate holder in a twin stage apparatus). The apparatus also includes a position disturbance correction system for correcting a position of the first substrate holder with respect to the patterned projection beam due to the influence of gas pressure differences or gas movements, caused by movements of the movable part. A related device manufacturing method is also presented in which, during the exposure of a first substrate, the position thereof is corrected by means of position disturbance correction system.